



*DSW*  
*[Signature]*

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q77490

Fumiyuki NISHIYAMA, et al.

Appln. No.: 10/669,603

Group Art Unit: 1713

Confirmation No.: 1317

Examiner: Satya B. Sastri

Filed: September 25, 2003

For: POSITIVE RESIST COMPOSITION AND PATTERN FORMATION METHOD USING  
THE SAME

**RESPONSE UNDER 37 C.F.R. § 1.111**

**MAIL STOP AMENDMENT**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated December 19, 2005, please consider the remarks as submitted herewith on the accompanying pages. A Petition and payment for a one month extension of time are being filed herewith, making this Response due on or before April 19, 2006.

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